Plan for Laser System @ Kyushu

ECAL Meeting in Tokyo 2012/12/18

Yuji Sudo (Kyushu University)

Motivation

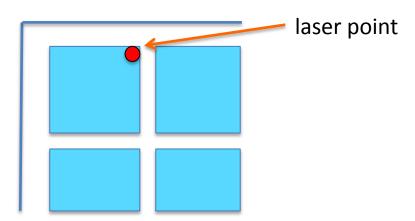
Microscope + Laser

- → make small radius laser light ~10µm
- → We can inject laser light anywhere in one pixel
- → Cross talk measurement, Edge effect

High power Laser

→ We can control number of e-h pair production by adjusting the yield of laser light



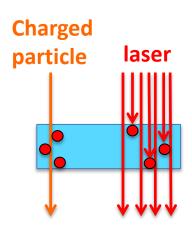


Signal Production by Infrared Laser

Wave length **1064 nm = 1.16 eV**

Energy gap of Si = 1.12 eV

Average production energy of e-h pair = 3.6 eV



Almost all laser light go through a Si sensor, but they can make e-h pair a certain probability.

→ We can make e-h pair uniformly in a sensitive area.

Spec. of The Laser



CRYLAS GmbH

DSS1064-Q2 (Class 3B)

Wave length : 1064 nm

Pulse width : $\sim 1.5 \text{ ns}$

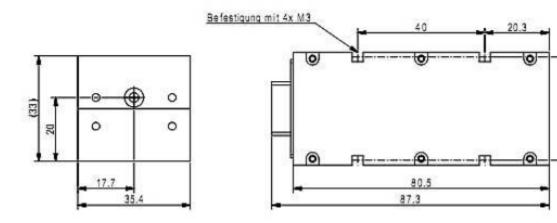
Pulse energy : $> 20 \mu J/pulse$

~ 10¹⁴ photons/pulse

Peak power : > 13kW

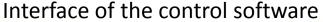
Reputation rate: 1 ~ 10kHz

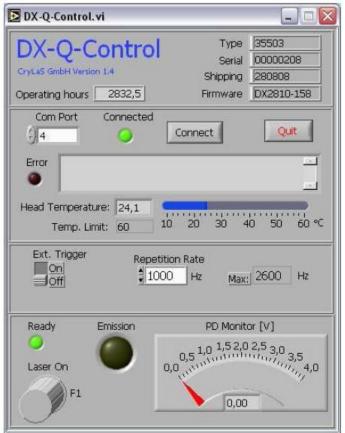
87.3 x 35.4 x 33 mm



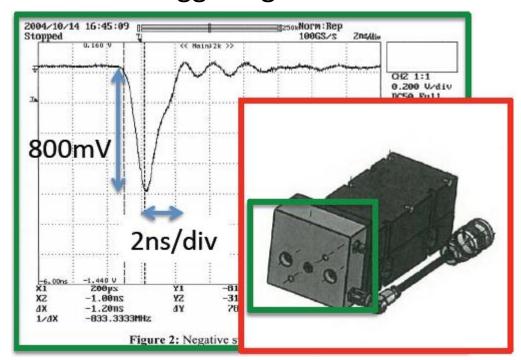
How to Control

- We can easily control the laser reputation rate with Windows software.
- There is a triggering system as an option of the laser.
- A trigger signal is negative 800 mV and 2ns width





Trigger signal

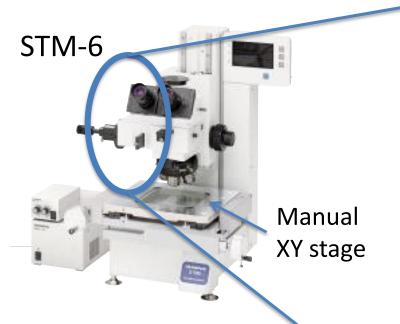


Optical system 1: Microscope

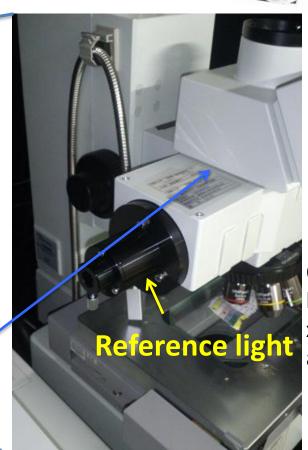
Olympus: STM-6



CCD camera

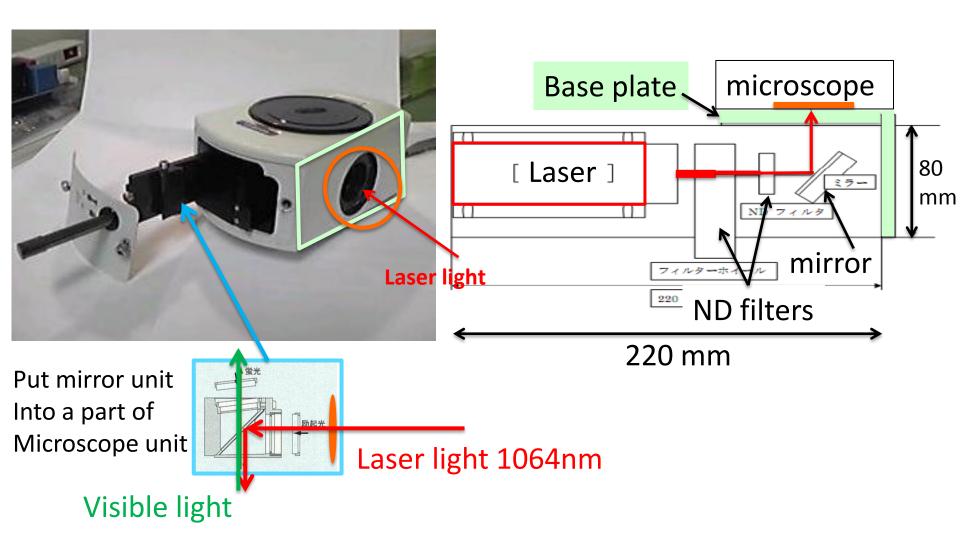






Objective lens x5, x20 and x100

Optical System 2 : Light Guide



We have to

- make a new Si sensor box optimized for the laser system
- make a signal read out system
- prepare daq system